

ABSTRACT OF THE DISCLOSURE

A first antireflection film is formed on the surface of an underlying substrate, the first antireflection film suppressing reflection in an absorption mode. A second antireflection film is formed on the first antireflection film, the second
5 antireflection film suppressing reflection in a countervailing interference mode. A cap film is formed on the second antireflection film. A photosensitive resist film is formed on the cap film. A latent image is formed in the photosensitive resist film by exposing the photosensitive resist film to light having a first
wavelength. The exposed resist film is developed. Even if the resist film is
10 ashed and resist is again coated, the initial reflectivity lowering effects can be retained.